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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION N
10/707,561	12/22/2003	Mu-Jung Wu	LKSP0034USA	1560
27765 7.	590 10/18/2004		EXAM	INER
NAIPO (NORTH AMERICA INTERNATIONAL PATENT OFFICE)			NGUYEN, DUNG V	
P.O. BOX 506 MERRIFIELD		A 22116	ART UNIT	PAPER NUMBER
	, =====		3723	
			DATE MAIL ED: 10/19/200/	•

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)
	10/707,561	WU ET AL.
Office Action Summary	Examiner	Art Unit
	Dung V Nguyen	3723
The MAILING DATE of this communication Period for Reply	appears on the cover sheet w	ith the correspondence address
A SHORTENED STATUTORY PERIOD FOR RETHE MAILING DATE OF THIS COMMUNICATIO - Extensions of time may be available under the provisions of 37 CFF after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a - If NO period for reply is specified above, the maximum statutory per - Failure to reply within the set or extended period for reply will, by state Any reply received by the Office later than three months after the material patent term adjustment. See 37 CFR 1.704(b).	N. R. 1.136(a). In no event, however, may a seriely within the statutory minimum of thir iod will apply and will expire SIX (6) MON atute, cause the application to become Al	reply be timely filed ty (30) days will be considered timely. ITHS from the mailing date of this communication. BANDONED (35 U.S.C. § 133).
Status		
1) Responsive to communication(s) filed on _	·	
2a) This action is FINAL . 2b) ⊠ T	his action is non-final.	
3) Since this application is in condition for allow	wance except for formal mat	ters, prosecution as to the merits is
closed in accordance with the practice unde	er <i>Ex parte Quayle</i> , 1935 C.D). 11, 453 O.G. 213.
Disposition of Claims		
4)⊠ Claim(s) <u>1-20</u> is/are pending in the applicati	ion.	
4a) Of the above claim(s) is/are without		
5) Claim(s) is/are allowed.		
6)⊠ Claim(s) <u>1-20</u> is/are rejected.		
7) Claim(s) is/are objected to.		
8) Claim(s) are subject to restriction an	d/or election requirement.	
Application Papers		
9) The specification is objected to by the Exam	iner.	
10) The drawing(s) filed on is/are: a) a		by the Examiner.
Applicant may not request that any objection to		-
Replacement drawing sheet(s) including the con		
11) The oath or declaration is objected to by the	Examiner. Note the attache	d Office Action or form PTO-152.
Priority under 35 U.S.C. § 119		
12) Acknowledgment is made of a claim for fore	ign priority under 35 U.S.C.	§ 119(a)-(d) or (f).
a) ☐ All b) ☐ Some * c) ☐ None of:		, . ,
1. Certified copies of the priority docum	ents have been received.	•
2. Certified copies of the priority docum	ents have been received in A	application No
3. Copies of the certified copies of the p	riority documents have been	received in this National Stage
application from the International Bur	eau (PCT Rule 17.2(a)).	
* See the attached detailed Office action for a	list of the certified copies not	received.
Attachment(s)	_	
 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) 	4) 🔲 Interview : Paper No(Summary (PTO-413) s)/Mail Date

Paper No(s)/Mail Date 8/27/04.

3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)

6) Other: ____.

5) Notice of Informal Patent Application (PTO-152)

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DETAILED ACTION

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 1-3 and 10-19 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ishikawa et al (USPN 6,257,966) in view of Togawa et al (USPN 6,319,105). Ishikawa et al discloses a wafer grinding apparatus 10 comprising a wafer-transporting device 28 for transporting a wafer 26, a suction pad 35 having a first surface and a second surface, the second surface being flexible for sucking the wafer 26, a transporting mechanism connected to the first surface of the suction pad for transporting the wafer 26, an air intake line, an air suction device connected to the air intake line for pumping air, wherein the suction pad 35 comprises a pedestal positioned on the transport mechanism and contains an opening connected to an end of the air intake line, a first table and a second table for situating the wafer 26, wherein the wafertransporting device 28 is utilized for moving the wafer 26 from the first table to the second table, a parking region 22 for parking the suction pad 35, wherein the first table is selected from a group consisting of a positioning table 16, a grinding table 50, and a cassette table 14, wherein the second table is selected from a group consisting of a positioning table 16, a grinding table 50, and a cassette table 14 (note Fig. 1-3, col. 3, line 50 to col. 6, line 2). However, Ishikawa does not discloses a first nozzle for ejecting

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a liquid to the first surface of the suction pad for cleaning the first surface, a second nozzle for ejecting a liquid to the second surface of the suction pad and wafer for cleaning the second surface and the wafer. Togawa et al discloses a first nozzle 42 for ejecting a first liquid to the first surface of the suction pad and a second nozzle 44 for ejecting a second liquid to the second surface of the suction pad and wafer for cleaning the second surface and the wafer, wherein the second nozzle 44 comprises a spray nozzle, wherein the first and second liquid comprises water (note Fig. 1-3, abstract, col. 2, lines 17-46, col. 3, line 30 to col. 4, line 15). It would have been obvious to one having ordinary skill in the art at the time the invention was made to modify the wafer grinding apparatus of Ishikawa et al the cleaning device including the first and second nozzles of Togawa et al in order to obtain high quality polishing by minimizing surface damage caused by contaminants originating from the suction pad.

3. Claims 4-9 and 20 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ishikawa et al (USPN 6,257,966) in view of Togawa et al (USPN 6,319,105) as applied to claims 1-3 above. Ishikawa et al modified by Togawa does not disclose expressly a flexible suction tray, a plurality of equally spaced flexible suction trays, elastic ring and transport mechanism comprises a T-shaped arm. At the time the invention was made, it would have been an obvious matter of design choice to a person of ordinary skill in the art to include a flexible suction tray, a plurality of equally spaced flexible suction trays, elastic ring or a T-shaped arm because Applicant has not disclosed that a flexible suction tray, a plurality of equally spaced flexible suction trays, elastic ring and T-shaped arm provides an advantage, is used for a particular purpose,

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or solves a stated problem. One of ordinary skill in the art, furthermore, would have expected Applicant's invention to perform equally well with a suction pad or a flexible suction tray, a plurality of equally spaced flexible suction trays, elastic ring because the suction pad or a flexible suction tray, a plurality of equally spaced flexible suction trays, elastic ring performs the same function of supporting the wafer when the wafer is sucked by vacuum suction and a T-shaped arm performs the same function of transporting a wafer between the tables. Therefore, it would have been an obvious matter of design choice to modify to obtain the invention as specified in claims 4-9.

Conclusion

- 4. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Hirata, Yoshida et al and Wada et al are cited to show wafer grinding apparatus having cleaning device.
- 5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Dung V Nguyen whose telephone number is 703-305-0036. The examiner can normally be reached on M-F, 6:30-3:00.
- 6. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Joseph J Hail can be reached on 703-308-2687. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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7. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic

DVN October 15, 2004

Business Center (EBC) at 866-217-9197 (toll-free).

DUNG VAN NGUYEN PRIMARY EXAMINER

Imy van hympul